



Faculty of Mechanical Engineering Institute of Materials Science, chair "materials science and nanotechnology"

Silicon-Nanowire Field Effect Transistors as Bio-Sensors

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Thesis: sensing with modulation of Schottky barriers?

Single nanowire FET with intruded Ni contacts

- annealing leads to axial diffusion of Ni into the nanowire
- metallic NiSi₂ is formed with a atomic sharp interface to the intrinsic silicon of the wire





- atomic sharp metal-semiconductor interface poses defined Schottky barriers (SB-FET)
- effective manipulation of barrier height with applied electric fields (gate voltage) is possible
- binding events of target and probe molecules near Schottky barriers lokally bend bands and lower energy barriers for electrons or holes

Nanowire growth via VLS (vapor liquid solid)

- bottom up synthesis of silicon nanowires in CVD furnace via VLS method with silane as precursor
- Gold particles with a diameter of 20nm made by Turkevich method serve as catalyst
- growth time of 10min at 450°C with a diluted silane gas (SiH₄/H₂ = 1/10)
 flow of 200sccm (60Torr) leads to 7-10µm long monocrystalline silicon nanowires









Electrical characteristics of single nanowire FETs

Back gated single nanowire FET

- 20nm thermal silicon oxide gate dielectric, source-drain (SD) voltage 0.5V
- (CH₂)₃NH₂ (alkane chain) terminated
 wires show ambipolar behaviour
- untreated wires behave like p-doped wires (unipolar behaviour)
- totally different IV characteristics, not just a simple shift like it is expected for a change in surface charge



Suggested mechansim

surface Fermi level pinning or

Creation of parallel arrays of nanowire FETs

Increase of sensitive area and signal amplitude compared to single nanowire FETs



alignment of nanowires with contact printing technique to obtain ordered arrays horizontally on silicon oxide



top-down lithographical methods for defining Ni contacts on nanowire arrays
 interdigitated fingers design for source/drain contacts

SEM picture of source/drain contacts

SEM picture of contacted nanowires





intrinsic nanow



"p-doped" nanowire

"doping"(charge transfer) due to polar molecules like H₂0

- "p-doped" nanowires: lower barrier for holes, higher barrier for electrons lead to rectified charge transport
- alkane chains shield from polar molecules and possible charge transfer





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